

Far-Infrared Spectroscopy of Thin Oxide Films

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INTRODUCTION

Our work at beamline 1.4.2 has involved the setting-up and use of Fourier-transform infrared (FTIR) spectroscopy in the range of 20-100 cm^{-1} to complement lower-frequency time-domain Terahertz (TD-THz) studies of thin films of the oxides SrRuO_3 and $\text{Bi}_2\text{Sr}_2\text{CaCu}_2\text{O}_{8+\delta}$. We have demonstrated stable measurement in the desired frequency range, have characterized the optical properties of the NdGaO_3 and LaAlO_3 substrates on which the two films, respectively, were grown, and have obtained transmission data for SrRuO_3 which upon further analysis may help to illuminate the oxide's non-Fermi-liquid electrical properties.

SYSTEM CAPABILITIES

The largest portion of our work at beamline 1.4.2 this year has been the adaptation of the beamline's Bruker IFS 66v/S FTIR system to the configuration necessary for far-infrared measurements of thin films. We installed, aligned, and calibrated a Janis cold-finger cryostat, on which the thin-film samples are mounted for measurement. This cryostat allows us to control the samples' temperatures in the range of approximately 9 K to 300 K. We aligned the special beamsplitters (Mylar of thickness 23 μm and 50 μm) necessary for far-IR measurements, installed a power supply, and tested the operation of an Infrared Laboratories bolometer, a LHe-cooled infrared detector with an optical low-pass filter at 100 cm^{-1} . We found that the system provides data with an excellent signal-to-noise ratio for frequencies of 20-100 cm^{-1} ; see figure 1. Moreover, a single beamsplitter (23 μm) provides data over the entire range, so that a sample's far-

IR transmission can be determined in one experiment.

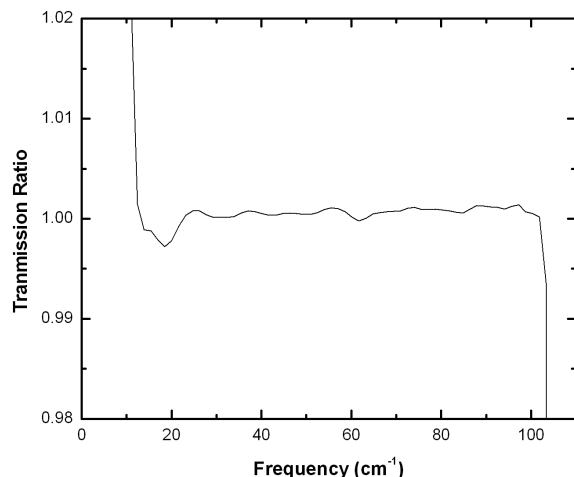
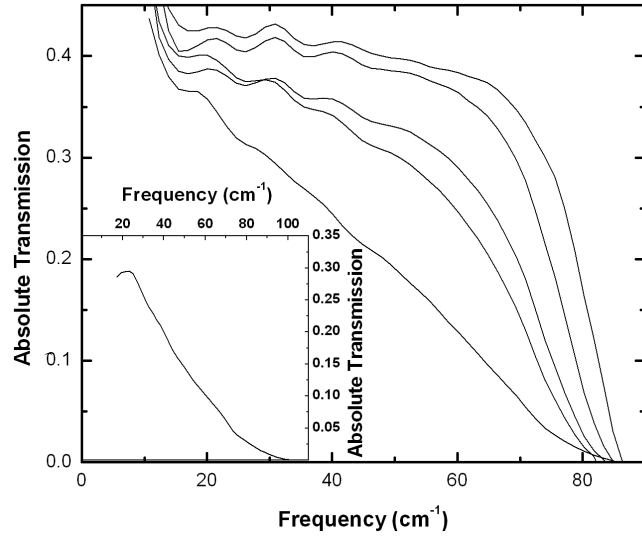


Figure 1: Measurement stability. The curve shown is the ratio of two consecutive sets of data, each collected for approximately 1 minute, with the source and external conditions held constant. The smallness of the deviations from unity shows excellent measurement stability in the range 20-100 cm^{-1} . The deviation below that range arises from opacity of the beamsplitter, and that above arises from a low-pass filter.

CHARACTERIZATION OF SUBSTRATES

Because thin films are grown on substrates, the optical transmission of a film must be normalized by that of the substrate. We measured the absolute transmission of the NdGaO_3 and LaAlO_3 substrates on which the SrRuO_3 and $\text{Bi}_2\text{Sr}_2\text{CaCu}_2\text{O}_{8+\delta}$ films, respectively, were grown; the results



appear in figure 2. We found that both substrates are opaque at frequencies above $\sim 100 \text{ cm}^{-1}$; measurement using an unfiltered detector showed that this opacity is intrinsic to the substrates, and not an artifact of the bolometer's low-pass filter. This opacity limits the possible bandwidth of optical measurements of films grown on these substrates.

Figure 2: Infrared transmission of NdGaO_3 substrate. From top to bottom: $T = 9 \text{ K}$, 65 K , 110 K , 150 K , 300 K . The curves for $T < 300 \text{ K}$ were fit to the form of the transmission arising from a single-oscillator absorption at approximately 90 cm^{-1} , as described in the text. **Inset:** The transmission of the LaAlO_3 substrate at $T = 300 \text{ K}$ is shaped similarly to that of NdGaO_3 . The transmission of LaAlO_3 rises above 1000 cm^{-1} (not shown).

Our measurements of a film yield the ratio, T , of the transmission of the film-substrate complex to that of the substrate alone; we seek to fit the measured T to that arising from a theoretical form for the complex electrical conductivity, σ , of the film. In the thin-film approximation, for a substrate of index of refraction n , T is given by:

$$T = |(n+1)/(n+1+\sigma d Z)|^2$$

where d is the thickness of the substrate, and Z is 377Ω . In order to perform the desired fit both the real and imaginary parts of n must be known, but both cannot be determined from measurements of optical transmission over a finite frequency range. However, we found that the measured transmission of NdGaO_3 (fig. 2) fits well to the form arising from a single-oscillator absorption at approximately 90 cm^{-1} , particularly for the lower temperatures; only the width of the oscillator was found to vary with temperature. We thus calculated the full complex n from the single-oscillator model.

CHARACTERIZATION OF SrRuO_3 FILMS

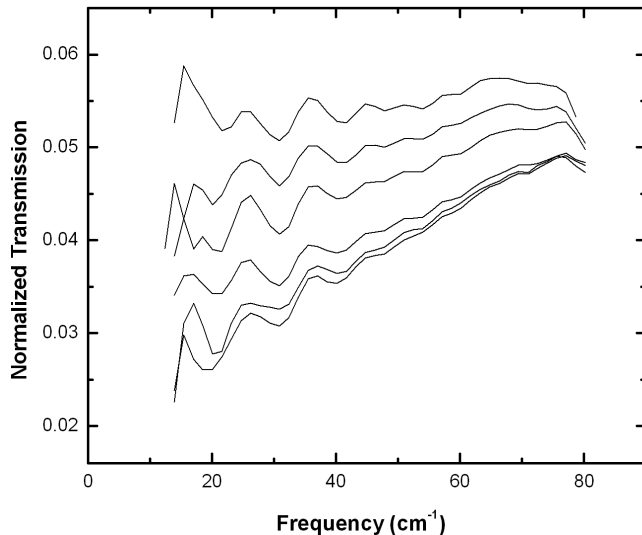


Figure 3: Infrared transmission of SrRuO_3 film, normalized by the transmission of the substrate. From top to bottom: $T = 65 \text{ K}$, 55 K , 45 K , 35 K , 25 K , 9 K . These curves are being fit to a form arising from non-fermi-liquid conductivity (see text). It is expected that the temperature dependence of the infrared transmission will reflect the temperature dependence of the inverse scattering rate, τ , which was determined by TD-THz methods.

The electrical properties of SrRuO_3 have attracted attention [1,2] because of the material's magnetic properties [3,4], and because of its similarities to the cuprate high- T_c superconductors. Recent measurements in the range $100\text{-}1000 \text{ cm}^{-1}$

[1] suggest non-Fermi-liquid electrical behavior, a behavior also thought to exist in the cuprates. We have measured the transmission of SrRuO₃ films at various temperatures; some of these data appear in figure 3. We are in the process of fitting these curves to a form for the transmission which arises from non-Fermi-liquid conductivity, σ , suggested by Ioffe and Millis [5].

A critical aspect of this fitting process is the connection with TD-THz data taken at lower frequencies. The inverse scattering rate τ , a parameter of the electrical conductivity, is given by $\tau = (d/d\omega) (\sigma_i/\sigma_r)$, where ω is the frequency, and σ_r and σ_i are the real and imaginary parts of σ , respectively. Since TD-THz measurements yield both σ_r and σ_i , our collaborators [6] have been able to accurately determine τ for temperatures below 70 K. It is expected that the temperature dependence of τ will be consistent with the temperature dependence of our far-infrared data in a non-Fermi-liquid model of the conductivity.

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